

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|------|--|---|------------------|---------|------------------|
| L1 | 994 | ((dielectric or isolat\$4) adj3 (layer or coat\$4)) same (article or wafer or substrate or mask or reticle or object or target) same electrostatic\$4 same electrode | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/29 13:29 |
| L2 | 900 | ((dielectric) adj3 (layer)) same (article or wafer or substrate or mask or reticle or object or target) same electrostatic\$4 same electrode | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/29 13:29 |
| L3 | 177 | 2 and (clamp\$4 near9 (article or reticle or mask or wafer or substrate or object or target)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/29 13:30 |
| L4 | 13 | 3 and ((detect\$4 or measur\$4 or sens\$4 or determin\$4) near5 (presence or absence) near5 (article or wafer or substrate or article or object or target)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/29 13:54 |
| L5 | 33 | 3 and (protrusion or projection) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/29 14:50 |
| L6 | 61 | 3 and (dielectric near9 (SiO or silic\$4 or SiN)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/29 14:59 |
| L7 | 33 | 3 and 5 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2005/07/29 14:59 |